

TSMC-00-023



October 6, 2000

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To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572  
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Poughkeepsie, N.Y. 12603

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Subject:

Serial No. 09/629,213 07/31/00

Chie-Chi Chen, Wen-Hsiang Tseng,  
Sheng-Liang Pan, Jen-Shiang Fang

PHOTORESIST STRIPPER USING NITROGEN  
BUBBLER

Grp. Art Unit: 1746

MARICOFF

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 4,251,317 to Foote, "Method of Preventing Etch  
Masking During Wafer Etching", discloses a gas bubbler in  
combination with a wafer cassette rotation within a wet wafer  
cleaning tank.

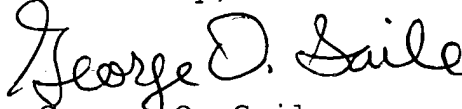
U.S. Patent 5,868,898 to Liu et al., "Fluid Dispensing Device for Wet Chemical Process Tank and Method of Using", discloses a wet wafer cleaning tank with a fluid distributor to agitate the stripper and form bubbles.

U.S. Patent 5,704,981 to Kawakami et al., "Processing Apparatus for Substrates to be Processed", recites a buffer plate for distributing gas in a reactor.

U.S. Patent 5,954,885 to Ohmi, "Cleaning Method", discloses a cleaning method using wet tanks and ultrasound.

U.S. Patent 5,464,480 to Matthews, "Process and Apparatus for the Treatment of Semiconductor Wafers in a Fluid", discloses a gas diffuse for a organic stripping/cleaning tank.

Sincerely,

A handwritten signature in cursive script that reads "George O. Saile". The signature is written in dark ink and is positioned above the printed name and registration number.

George O. Saile,  
Reg. No. 19572